914 892 6363 TO

I hereby certify that this correspondence is being deposited by FACSIMILE to the Commissioner of Patents and Trademarks, Washington, DC on April 15, 2002 by Colleen Dew.

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE Group Art Unit 2822

In re application of

April 15, 2002

Axel Brintzinger et al.

Examiner: Monica Lewis

Serial No.: 09/873,537

Filed: June 4, 2001

IBM Corporation

Dept. 18G/Bldg, 300-482

Title: DUAL DAMASCENE ANTI-FUSE

2070 Route 52

WITH VIA BEFORE WIRE

Hopewell Junction, NY

12533-6531

<u>Am</u>endment

Commissioner for Patents and Trademarks Washington, D.C. 20231

Sir:

Kindly amend the claims as follows:

- 22. (amended) An interconnect structure in which an anti-fuse dielectric is 1 2 formed therein comprising:
- a substrate having a first level of electrically conductive features;
- a patterned anti-fuse dielectric layer formed on said substrate, wherein said patterned anti-fuse dielectric layer includes an opening to at least one 5
- of said first level of electrically conductive features;